

X = 4.4mm Y = 2.28mm

Product Features

■ RF frequency: 18 to 23 GHz

■ Linear Gain: 20 dB typ.

■ Psat: 38 dBm typ.

■ Efficiency @ P3dB > 30 %

■ Die Size: < 10.032 sq. mm.

■ 0.2um GaN HEMT

■ 4 mil SiC substrate

■ DC Power: 28 VDC @ 544 mA

Performance Characteristics (Ta = 25° C)

Specification	Min	Тур	Max	Unit	
Frequency	18		23	GHz	
Linear Gain	19	23		dB	
Input Return Loss	4	11		dB	
Output Return Loss	6	11		dB	
P1db		36		dBm	
Psat	37.5	38.5		dBm	
PAE @ Psat		30		%	
Vd1, Vd2		28		V	
Vg1		-3.5		V	
Vg2		-3.5		V	
ld1		144		mA	
ld2		400		mA	

Applications

- Military SatCom
- Phased-Array Radar Applications
- Point-to-Point Radio
- Point-to-Multipoint Communications
- Terminal Amplifiers

Product Description

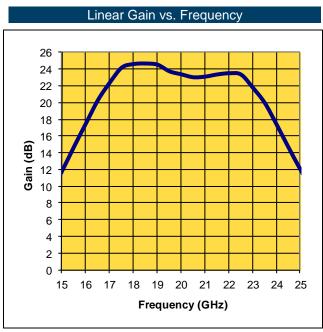
The APN149 monolithic GaN HEMT amplifier is a broadband, two-stage power device, designed for use in Point-to-Point and Multipoint Digital Radios, Military SatCom and Radar Applications. To ensure rugged and reliable operation, HEMT devices are fully passivated. Both bond pad and backside metallization are Au-based that is compatible with epoxy and eutectic die attach methods.

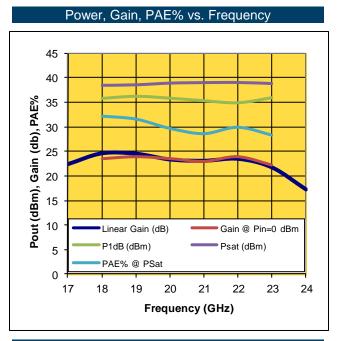
Absolute Maximum Ratings (Ta = 25°C)

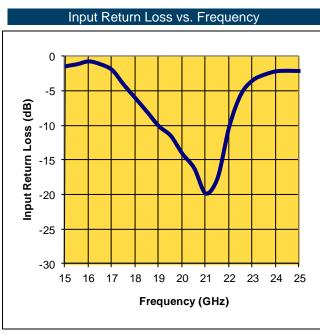
Parameter	Min	Max	Unit	
Vd1, Vd2	20	28	V	
ld1		144	mA	
ld2+ld2a		400	mA	
Vg1, Vg2	-5	0	V	
Input drive level		TBD	dBm	
Assy. Temperature		300	deg. C	
(TBD seconds)				

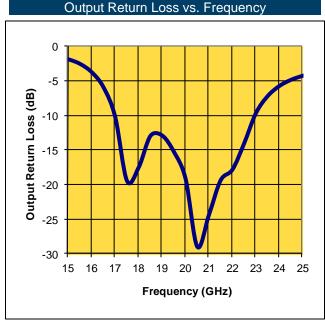


Measured Performance Characteristics (Typical Performance at 25°C) Vd = 28.0 V, Id1 = 144 mA, Id2 = 400 mA *





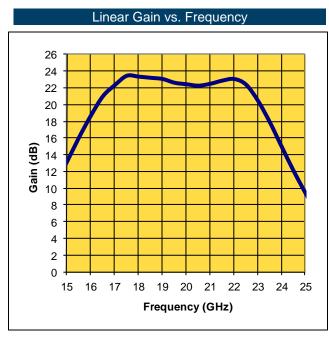


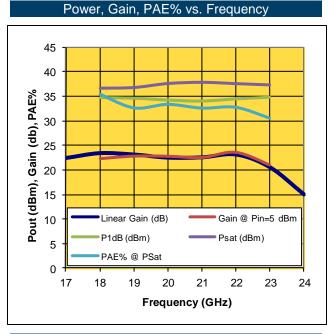


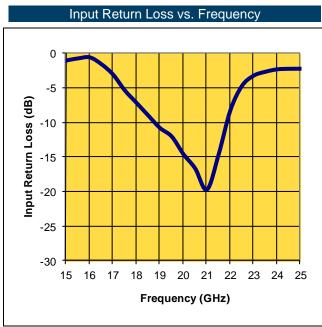
^{*} Pulsed-Power On-Wafer

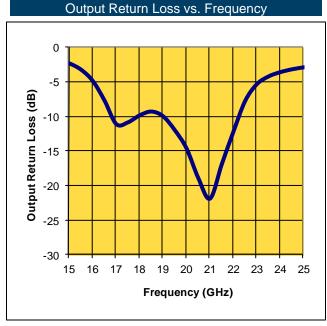


Measured Performance Characteristics (Typical Performance at 25°C) Vd = 20.0 V, Id1 = 144 mA, Id2 = 400 mA *





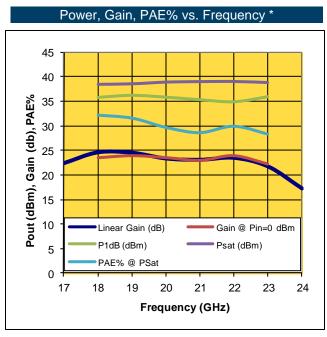


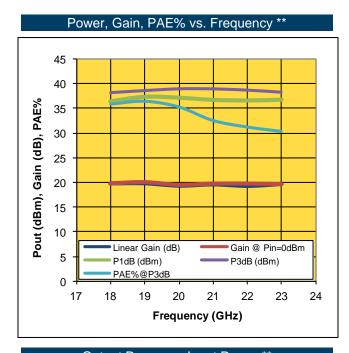


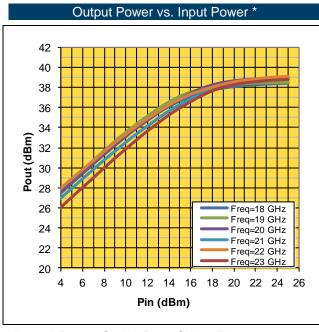
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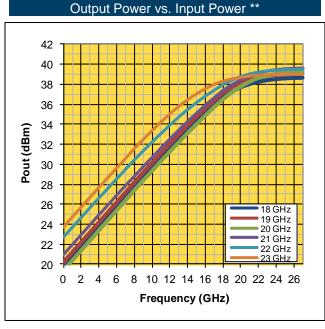


Measured Performance Characteristics (Typical Performance at 25°C) Vd = 28.0 V, Id1 = 144 mA, Id2 = 400 mA





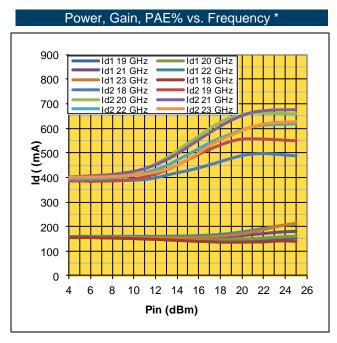


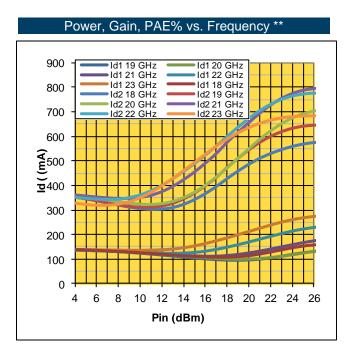


^{*} Pulsed-Power On-Wafer, **CW in Fixture



Measured Performance Characteristics (Typical Performance at 25°C) Vd = 28.0 V, Id1 = 144 mA, Id2 = 400 mA





Thermal Properties

Preliminary Thermal Properties with die mounted with 1mil 80/20 AuSn Eutectic to 25mil CuW Shim.

Conditions	Shim Boundary Temperature	Junction Temperature Tjc	Thermal Resistance θjc
Vd = 28V, Id1 = 140 mA *	25 °C	152.2 °C	7.8 °C/W
Id2 + Id2a = 727 mA *	50 °C	189.1 °C	8.6 °C/W
Pin=23.24 dBm	57.3 °C	200.0 °C **	8.78 °C/W
Pout=39.14 dBm			

^{*} Vd = 28.0 V, Idq1 = 144 mA, Id2q = 400 mA

^{*} Pulsed-Power On-Wafer, **CW in Fixture

^{**} Max recommended. Pre-qualification reliability testing indicates that MTTF in excess of 10⁵ hours can be achieved by ensuring Tjc is kept below 200°C.

APN149 18-23 GHz GaN Power Amplifier



Advance Datasheet Revision: January 2015

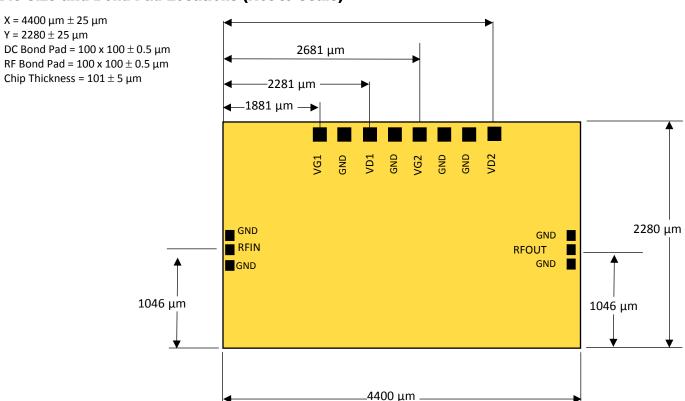
Measured Performance Characteristics (Typical Performance at 25°C) Vd = 28.0 V, Id1 = 144 mA, Id2 = 400 mA *

Freq GHz	S11 Mag	S11 Ang	S21 Mag	S21 Ang	S12 Mag	S12 Ang	S22 Mag	S22 Ang
12.0	0.699	43.964	0.779	-19.442	0.002	36.788	0.840	-130.950
12.5	0.692	27.965	1.003	-37.868	0.001	-113.227	0.863	-143.724
13.0	0.702	13.013	1.304	-56.793	0.003	115.571	0.867	-157.606
13.5	0.701	-6.259	1.756	-75.707	0.003	12.387	0.861	-170.158
14.0	0.743	-23.885	2.312	-97.113	0.002	116.066	0.854	176.435
14.5	0.753	-41.896	3.187	-118.651	0.003	53.407	0.822	163.141
15.0	0.809	-61.628	4.308	-141.688	0.004	79.825	0.789	149.562
15.5	0.843	-81.659	5.968	-168.862	0.006	45.166	0.716	133.098
16.0	0.886	-106.151	8.076	160.835	0.006	19.273	0.597	116.578
16.5	0.893	-125.821	10.849	129.080	0.009	-0.556	0.443	99.724
17.0	0.830	-154.023	13.070	90.315	0.010	-38.819	0.255	87.416
17.5	0.713	-169.316	15.259	52.758	0.011	-68.439	0.152	126.751
18.0	0.558	168.254	15.601	13.681	0.010	-102.665	0.242	138.228
18.5	0.460	164.497	15.149	-18.903	0.011	-131.466	0.284	127.812
19.0	0.338	151.417	15.094	-50.296	0.012	-168.802	0.274	112.392
19.5	0.304	151.107	14.549	-80.833	0.012	159.721	0.231	91.740
20.0	0.215	144.657	14.221	-108.869	0.014	128.038	0.164	82.177
20.5	0.206	125.765	13.863	-138.643	0.011	101.178	0.109	65.615
21.0	0.089	135.731	14.090	-166.063	0.013	87.099	0.090	93.235
21.5	0.091	41.988	14.418	163.337	0.018	51.402	0.135	93.307
22.0	0.190	-58.964	14.261	126.963	0.017	16.108	0.220	56.643
22.5	0.439	-77.160	13.245	89.725	0.015	-15.227	0.324	10.566
23.0	0.560	-109.180	10.993	51.085	0.013	-49.790	0.447	-28.152
23.5	0.724	-128.470	8.148	18.278	0.009	-71.583	0.541	-61.608
24.0	0.727	-148.562	5.919	-11.422	0.007	-100.505	0.595	-85.387
24.5	0.802	-160.957	4.218	-34.985	0.003	-131.781	0.629	-104.385
25.0	0.777	-170.382	3.155	-57.268	0.002	-89.706	0.661	-119.136
25.5	0.803	177.352	2.293	-77.195	0.002	-49.011	0.681	-130.378
26.0	0.789	172.098	1.807	-94.490	0.001	-29.848	0.713	-139.718
26.5	0.775	157.890	1.382	-113.016	0.004	-0.197	0.733	-148.879
27.0	0.811	158.238	1.094	-127.212	0.004	-55.666	0.747	-156.758
27.5	0.767	147.132	0.861	-144.501	0.005	-81.846	0.757	-163.728
28.0	0.830	142.237	0.689	-158.251	0.001	-63.247	0.785	-170.694

^{*} Pulsed-Power On-Wafer



Die Size and Bond Pad Locations (Not to Scale)



Biasing/De-Biasing Details:

Bias is single sided and is from the top only.

Listed below are some guidelines for GaN device testing and wire bonding:

- a. Limit positive gate bias (G-S or G-D) to < 1V
- b. Know your devices' breakdown voltages
- c. Use a power supply with both voltage and current limit.
- d. With the power supply off and the voltage and current levels at minimum, attach the ground lead to your test fixture.
 - i. Apply negative gate voltage (-5 V) to ensure that all devices are off
 - ii. Ramp up drain bias to ~10 V
 - iii. Gradually increase gate bias voltage while monitoring drain current until 20% of the operating current is achieved
 - iv. Ramp up drain to operating bias
 - v. Gradually increase gate bias voltage while monitoring drain current until the operating current is achieved
- e. To safely de-bias GaN devices, start by debiasing output amplifier stages first (if applicable):
 - i. Gradually decrease drain bias to 0 V.
 - ii. Gradually decrease gate bias to 0 V.
 - iii. Turn off supply voltages
- f. Repeat de-bias procedure for each amplifier stage

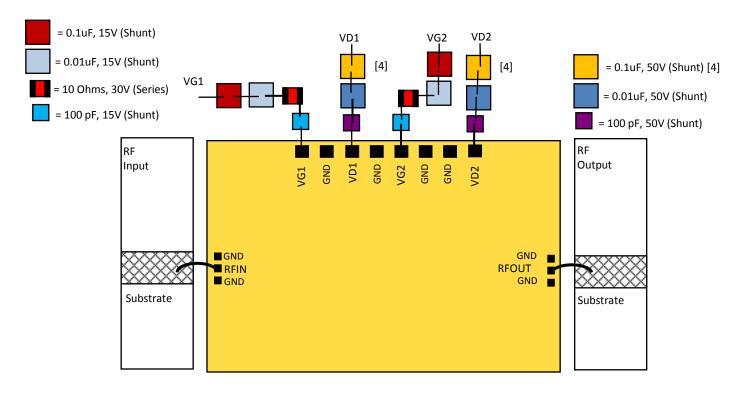
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Advance Datasheet
Suggested Bonding Arrangement



Recommended Assembly Notes

- 1. Bypass caps should be 100 pF (approximately) ceramic (single-layer) placed no farther than 30 mils from the amplifier.
- 2. Best performance obtained from use of <10 mil (long) by 3 by 0.5 mil ribbons on input and output.
- 3. Part must be biased from both sides as indicated.
- 4. The 0.1uF, 50V capacitors are not needed if the drain supply line is clean. If Drain Pulsing of the device is to be used, do **NOT** use the 0.1uF, 50V Capacitors.

Mounting Processes

Most NGAS GaN IC chips have a gold backing and can be mounted successfully using either a conductive epoxy or AuSn attachment. NGAS recommends the use of AuSn for high power devices to provide a good thermal path and a good RF path to ground. Maximum recommended temp during die attach is 320°C for 30 seconds.

Note: Many of the NGAS parts do incorporate airbridges, so caution should be used when determining the pick up tool.

CAUTION: THE IMPROPER USE OF AuSn ATTACHMENT CAN CATASTROPHICALLY DAMAGE GaN CHIPS.

PLEASE ALSO REFER TO OUR "Gan Chip Handling Application Note" BEFORE HANDLING, ASSEMBLING OR BIASING THESE MMICS!